

Please amend the subject application as follows:

IN THE CLAIMS

Please amend claims 1 and 3 and cancel claims 4-7:

1. (Currently amended) A plasma chamber comprising a lower electrode and an upper electrode, and used for dry-etching an LCD, comprising:

a main power supply comprising a main power source to generate a main voltage having a predetermined main frequency, and a first impedance matching circuit to impedance-match the main voltage;

a bias power supply comprising a bias power source to generate a bias voltage having a predetermined bias frequency, and a second impedance matching circuit to impedance-match the bias voltage;

at least one auxiliary power supply comprising an auxiliary power source to generate an auxiliary voltage having a predetermined frequency and a third impedance matching circuit to impedance-match the auxiliary voltage; and

a mixer connected to the first impedance matching circuit, the second impedance matching circuit, and the third impedance matching circuit, wherein the mixer receives and mixes the main voltage, the bias voltage, and the auxiliary voltage, and outputs [[a]] an unbranched mixed voltage of the main voltage, the bias voltage, and the auxiliary voltage to one of the lower electrode and the upper electrode,

wherein the bias frequency is lower than the main frequency.

2. (Canceled)

3. (Currently amended) The plasma chamber according to claim 1, wherein the mixer outputs the unbranched mixed voltage by adding the received voltages.

4-7. (Canceled)